

INFORMATION DISCLOSURE STATEMENT PTO-1449	Attv. Docket No. 042184	Serial No. New Appln. 10/797,596
	Applicant(s): Akira FUKUDA, et al.	
	Filing Date: March 11, 2004	Group Art Unit: 2821

U.S. PATENT DOCUMENTS

Examiner Initial	Document No.	Name	Date	Class	Subclass	Filing Date (If appropriate)
EA	AA	4,158,589	Keller et al.	06/19/79	156 345.46	
EA	AB	5,827,435	Samukawa	10/27/98	315 111.21	
EA	AC	5,928,528	Kubota et al.	07/27/99	118 723 E	
EA	AD	6,217,703	Kitagawa	04/17/01	156 345.33	
EA	AE	6,331,701	Chen et al.	12/18/01	315 111.81	

FOREIGN PATENT DOCUMENTS

	Document No.	Date	Country	Translation (Yes or No)	CLASS SUB
EA	AF	WO 01/06534	01/25/01	PCT	Abstract
EA	AG	WO 02/078407	10/03/02	PCT	Abstract

OTHER DOCUMENTS

EA	AH	J.M.E. Harper et al., "Low Energy Ion Beam Etching", J. Electrochem. Soc: SOLID-STATE SCIENCE AND TECHNOLOGY, Vol.128, No. 5, May 1981, pp. 1077-1083.
EA	AI	Harold R. Kaufman, "Technology of ion beam sources used in sputtering", J. Vac. Sci. Technol. 15(2), March/April 1978, pp. 272-276.
EA	AJ	Shoji KITAMURA, "Ion Engine (Direct Current Discharge Type)", J. Vac. Soc. Jpn. Vol. 45, No. 4, 2002, pp. 329-335.

Examiner	<i>Ephrem Alemu</i>	Date Considered	6-09-05
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